

**INFORMATION DISCLOSURE  
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APPLICATION  
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APPLICANT  
SHANMUGASUNDRAM et al.

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## U.S. PATENT DOCUMENTS

[illegible]

**OTHER ART** (Including Author, Title, Date, Pertinent Pages, Etc.)

	Boning, Duane et al. "Run-by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans.</i> October 1996. Vol. 19, No. 4. pp. 307-314.
	Moyne, James et al. "A Run-to-Run Control Framework for VLSI Manufacturing." <i>Microelectronic Processing '93 Conference Proceedings.</i> September 1993.
	Telfeyan, Roland et al. "Demonstration of a Process-Independent Run-to-Run Controller." <i>187<sup>th</sup> Meeting of the Electrochemical Society.</i> May 1995.
	Moyne, James et al. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Adv. Semiconductor Manufacturing Conference.</i> August 15, 1995.
	Moyne, James et al. "Adaptive Extensions to be a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology.</i> 1995.
	Sachs, Emanuel et al. "Process Control System for VLSI Fabrication."
	Chaudhry, Nauman et al. "Active Controller: Utilizing Active Databases for Implementing Multi-Step Control of Semiconductor Manufacturing." <i>University of Michigan.</i> pp. 1 - 24.
	Chaudhry, Nauman et al. "Designing Databases with Fuzzy Data and Rules for Application to Discrete Control." <i>University of Michigan.</i> pp. 1 - 21.
	Chaudhry, Nauman A. et al. "A Design Methodology for Databases with Uncertain Data." <i>University of Michigan.</i> pp. 1 - 14.
	Khan, Kareemullah et al. "Run-to-Run Control of ITO Deposition Process." <i>University of Michigan.</i> pp. 1 - 6.
	Moyne, James et al. "Yield Improvement @ Contact Through Run-to-Run Control."
	Kim, Jiyoun et al. "Gradient and Radial Uniformity Control of a CMP Process Utilizing a Pre- and Post-Measurement Strategy." <i>University of Michigan.</i>

**EXAMINER**

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

